

VCA Performa 300TM Wafer Surface Analysis Systems are specially designed for use in semiconductor and LED wafer processing quality control. The system provides quick and accurate contact angle/surface energy analysis on wafer surface to evaluate adhesion, cleanliness and coatings.

Applications:

- Coating assessment of the **HMDS** process
- Surface contamination detection
- Adhesive and primer preparation
- Coating uniformity
- Coating quality
- Surface cleanliness

Hardware Features

- High-resolution video camera with magnifying lens with high intensity
- all areas of the wafer
- high-performance video board for advanced image analysis and video capture

Software Features

- Automatic contact angle imaging and calculation
- Dynamic droplet capture (movie viewing of droplets)
- Surface energy (dynes/cm) analysis
- SPC (Statistical Process Control)
- Pendant Drop surface analysis



Dynamic Capture Window

Syringe Assembly

- Vertical Orientation
- Straight Needle
- Motorized Drive Mechanism
- 1.8 Degree Stepping Motor
- Syringe Head: Tilt back for safe and easy removal of large samples

Sample Platform

- Platform size and shape 12" Circular
- Sample size and shape 4", 6", 8", 12" circular Not wider than 12"
- Movement along the optical axis 6" by • hand sliding with lock
- Movement transverse to the optical axis 6" by dial
- Vertical traveling distance 2" by dial
- Rotating 360 degrees by hand with **Planary Bearing**

VCA Optima VCA 46 series (automatic mode)

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VCA Performa 300™

- LED lighting for precise image capture
- 300mm rotating stage, allows access to
- High-end PC is standard with
- Flat Screen Monitor